

## Claims

1. Optical device comprising reflecting means arranged on the optical path of an  
5 incident beam (10) emitted by a first optical source (7) so as to form a reflected  
light beam (12), and a second optical source (8) producing a second light beam  
(11) of different wavelength so that the reflected beam (12) and the second light  
beam (11) pass through a zone of the space (14) wherein an object to be  
analyzed is to be exposed, and reach a common sensor (13), optical device (6)  
10 characterized in that the reflecting means are arranged proximate to the optical  
path of the second beam (11).
2. Optical device according to claim 1, characterized in that the optical device (6)  
comprises means for deforming the reflecting means.  
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3. Optical device according to one of the claims 1 and 2, characterized in that the  
optical device (6) comprises means for orienting the reflecting means.
4. Optical device according to one of the claims 1 to 3, characterized in that the  
20 reflecting means are formed by a mirror (15).
5. Optical device according to claim 4, characterized in that an element (17)  
absorbing a part of a light radiation is arranged on the reflecting surface of the  
mirror (15).  
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6. Optical device according to any one of the claims 1 to 3, characterized in that  
the reflecting means are formed by a semi-reflecting plate (16).

7. Optical device according to claim 6, characterized in that the semi-reflecting plate (16) is arranged on an element (17) absorbing a part of a light radiation.
- 5 8. Optical device according to any one of the claims 1 to 7, characterized in that the optical device (6) comprises a collimating lens (19) common to the first and second sources (7, 8) and arranged at the intersection of the first incident beam (10) and of the second beam (11).
- 10 9. Optical device according to claim 8, characterized in that the collimating lens (19) is spherical.
10. Optical device according to any one of the claims 1 to 9, characterized in that a lens (20) is arranged between the zone of the space (14) wherein the object to be analyzed is to be exposed and the sensor (13).